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Correction

Correction: Panjan et al. Surface Topography of PVD Hard Coatings. *Coatings* 2021, *11*, 1387

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Error in Table

The authors wish to make the following correction to this paper [1]:

In the row "average deposition rate" of Table 1 (page 5) the unit "nm/s" must be replaced with the unit "nm/min". The corrected Table 1 appears below. The authors state that the scientific conclusions are unaffected. This correction was approved by the Academic Editor. The original publication has also been updated.

Table 1. Deposition methods and process parameters used for the preparation of PVD hard coatings. The deposition rates and ion current density are averages since all deposition techniques exhibited both spatial and temporal variations during a given deposition run as well as from one run to another run (depending on batching material).

	Deposition System	BAI 730	CC800/7	CC800/9 sinOx ML	AIPocket
Preheating	Heating method	Electron bombardment	Infrared heating	Infrared heating	Infrared heating
	Preheating temperature (°C)	450	450	450	450
Etching	Etching mode	DC	RF	MF/booster	pulsed DC
	Type of ions	Ar	Ar + Kr	Ar + Kr	Ar
	Negative substrate etching voltage (V)	200	200	650/200	300/400
	Etching time (min)	15	85 + 55 **	15/60	45
Deposition	Deposition method	Low-voltage electron beam evaporation	Magnetron sputtering	Magnetron sputtering	Cathodic arc evaporation
	Temperature (°C)	450	450	450	450
	Working gas	Ar + N_2	Ar + Kr + N_2	Ar + Kr + N_2	N_2
	Pressure of working gas (Pa)	0.2	0.75	0.66	4
	Deposition time (min)	80	165	200	45
	Negative substrate bias voltage (V)	125	95	90	70
	Average deposition rate * (nm/min)	50	20	20	85
	Average substrate current density (mA/cm^2)	3–5	~2	~2.5	-

* For twofold rotation of substrates, ** intermediate etching.

check for updates

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